

Radiation Assurance Test in BMTI

Dr. Zhao Yuanfu

Beijing Microelectronics Technology Institute

EEE Components Radiation Test Workshop

31st March – 1st April, 2016

Outline

- ◆ **A general BMTI introduction**
- ◆ **Using built-in self-test (BIST) structures for SEE test**
- ◆ **SEE failure analysis with laser**
- ◆ **Test method for distinguishing SEU and SET, and SET analysis**

Outline

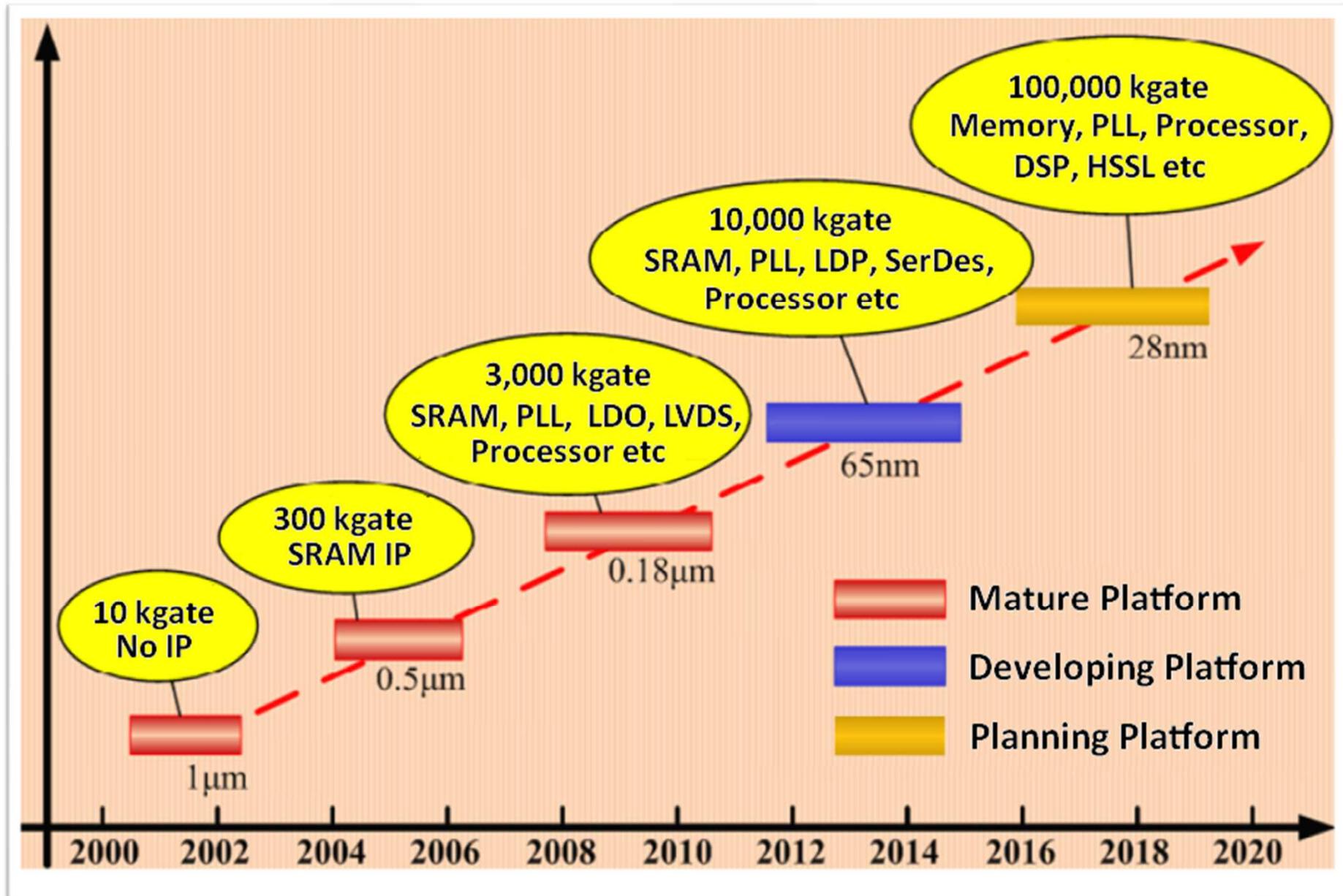
- ◆ **A general BMTI introduction**
- ◆ Using built-in self-test (BIST) structures for SEE test
- ◆ SEE failure analysis with laser
- ◆ Test method for distinguishing SEU and SET, and SET analysis

A General BMTI Introduction

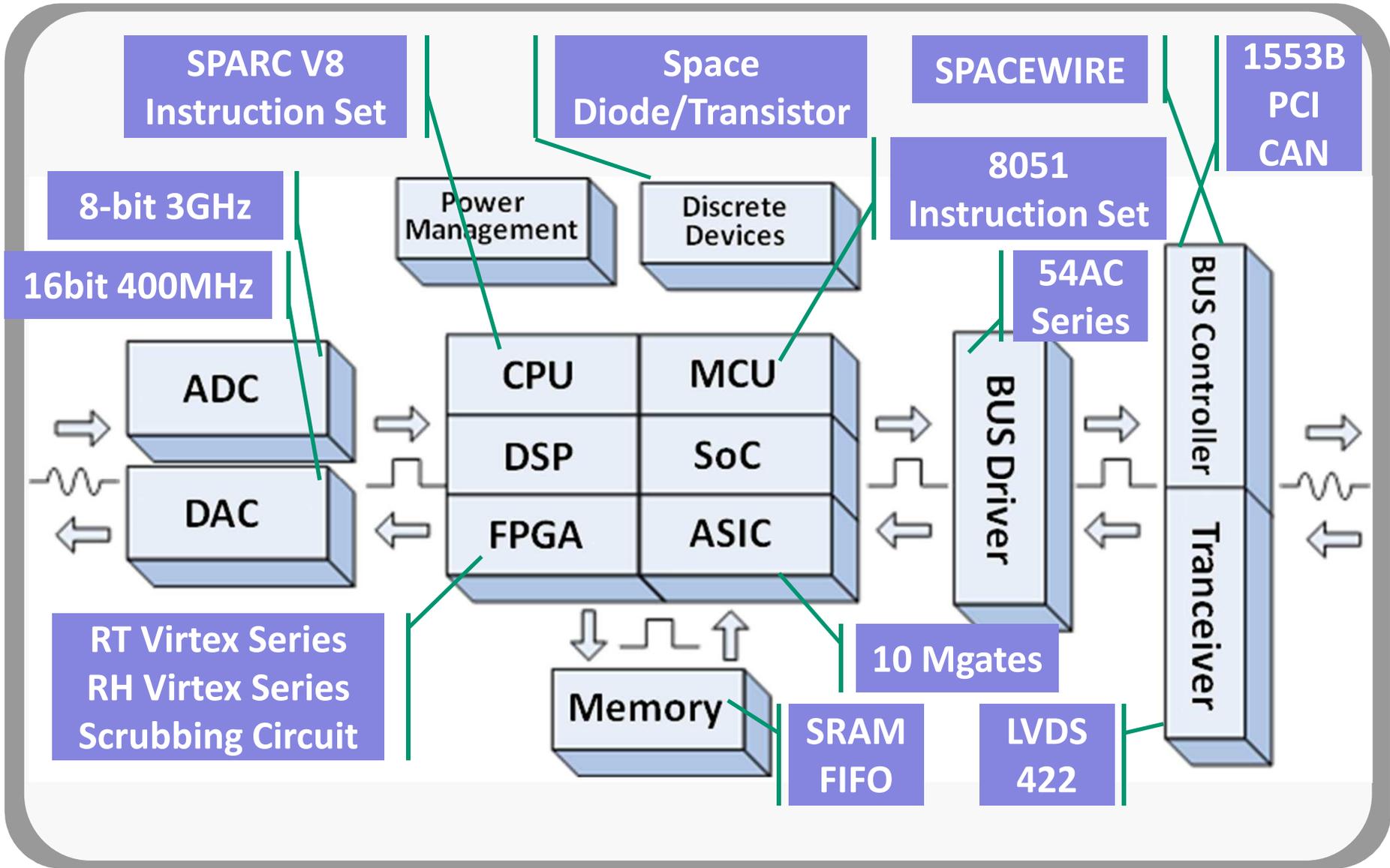
- ◆ **BMTI is a China leading organization in radiation-hardened microelectronics research**
- ◆ **Also the largest radiation-hardened IC provider in China**
- ◆ **The main achievements include:**
 - **Several high-reliability RH IC design platforms**
 - **A complete RH IC product family**
 - **Advanced packaging, testing, and 4-inch fab line**



BMTI's Radiation-Hardening Design Platforms



BMTI's Space IC Product Family



Packaging, Testing and Fab Lines

✓ Ceramic package line

- Up to 1,500 pins
- BGA/QFP/PGA/LCC/DIP/CCGA
- MCM/3-D packaging

✓ Testing line

- Up to 1,024 test channels
- Up to 1GHz test frequency
- FPGA/SoC/RF/ADC/DAC/Memory chips

✓ Reliability assessment

- Screen and Qualification Inspection
- Up to 25MHz Burn-in frequency
- Compliant with GJB548 (MIL-STD-883), GJB33 (MIL-PRF-19500)

✓ 0.8 μ m, 4-inch fab line

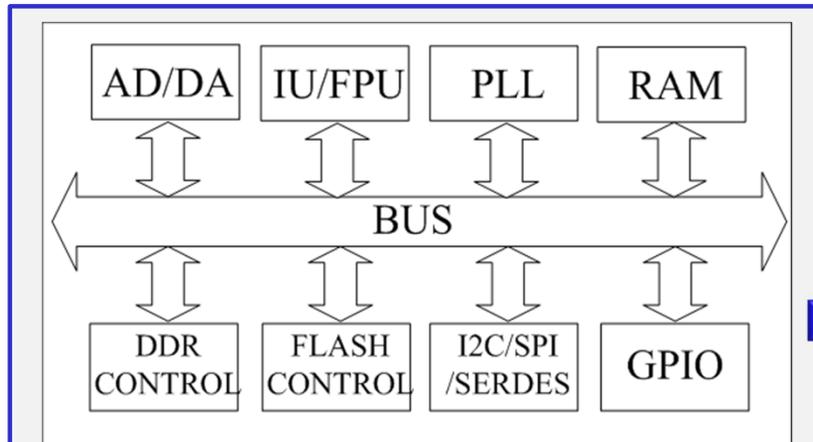
- Space diode/transistor/VDMOS
- MEMS
- Capable of processing 3,000 wafers/month



Outline

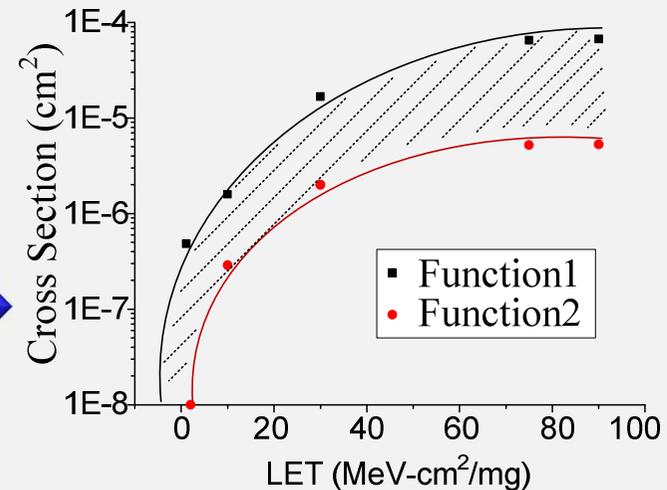
- ◆ A general BMTI introduction
- ◆ **Using built-in self-test (BIST) structures for SEE test**
- ◆ SEE failure analysis with laser
- ◆ Test method for distinguishing SEU and SET, and SET analysis

Problem with SEE testing of complex ICs



A typical complex IC

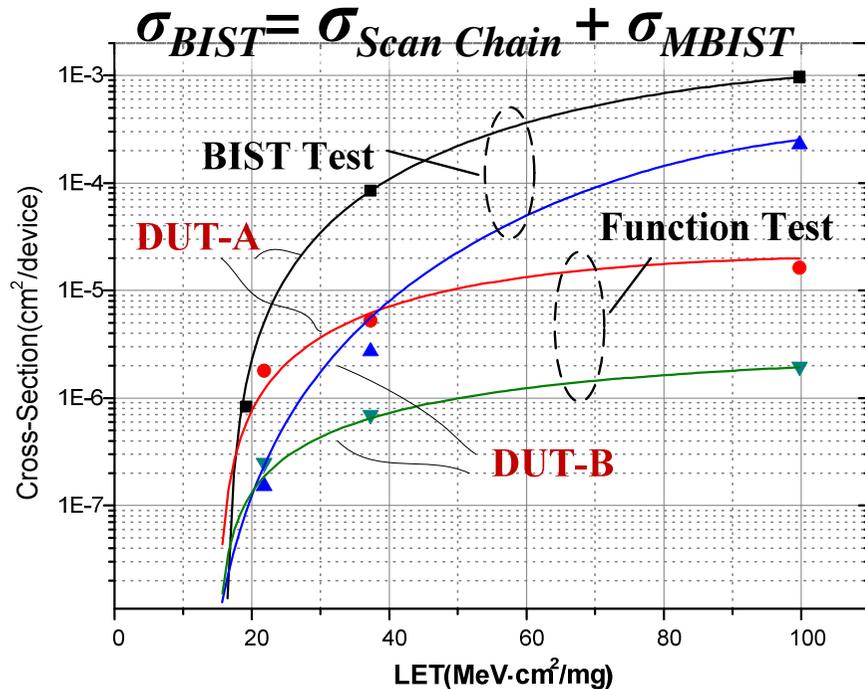
- ✓ **Many modules**
- ✓ **many function modes**



Different cross sections for different function

- **It is very difficult to evaluate and define the SEE hardness of a complex IC by limited function tests**
- **A simple method which can implement a worst-case test is needed**

Comparison between Function and BIST SEE test



Item Device	LET Threshold (MeV·cm ² /mg)	Saturation cross section (cm ² /device)
DUT-A BIST	13.6-22.2	9E-4
DUT-A Function		1.5E-5
DUT-B BIST		2E-4
DUT-B Function		2E-6

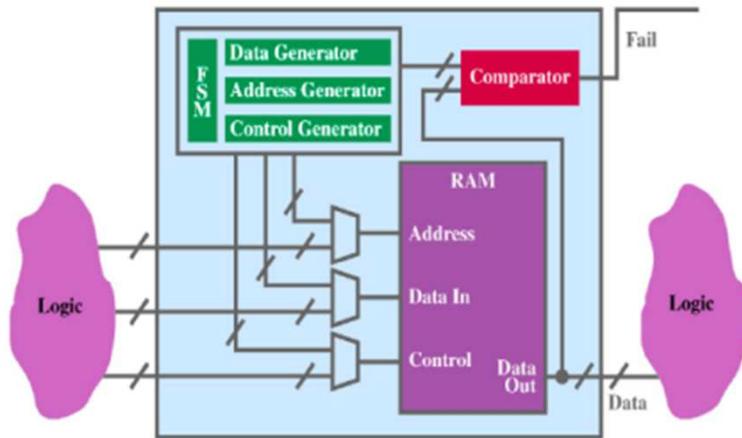
DUT-A and DUT-B are two 0.18 μ m rad-hard ICs

- σ_{BIST} is always greater than $\sigma_{Function}$
- SEE test with BIST is a worst-case test

BIST test result can be a conservative estimation of any function test results

Effective fluence in SEE test with MBIST

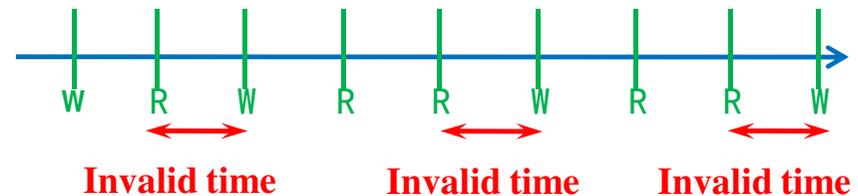
Memory BIST



- The sequence and timing of MBIST operation is determined by embedded arithmetic, but can't be adjusted
- Not all SEUs can be detected due to self refresh by write operation

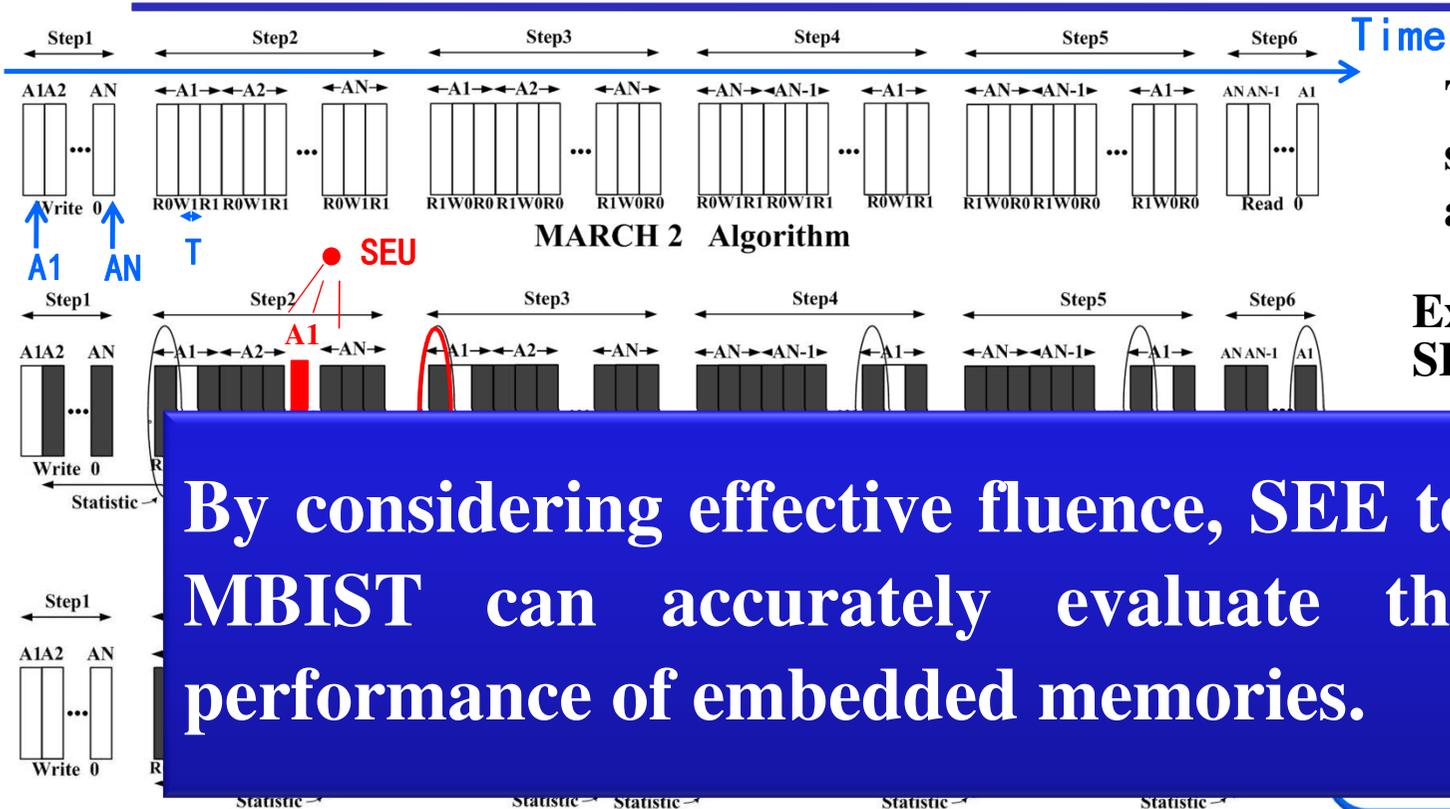
March-2 arithmetic:

1up - write 0
2up - read 0, write 1, read 1
3up - read 1, write 0, read 0
4down - read 0, write 1, read 1
5down - read 1, write 0, read 0
6down - read 0



Effective fluence should be calculated according to the MBIST arithmetic

Effective fluence in SEE test with MBIST



The W/R execution sequence of each addr(A1-AN)

Example: A1 and AN SEU Capture Process

By considering effective fluence, SEE test with MBIST can accurately evaluate the SEU performance of embedded memories.

Effective Time
Total Time

$$\frac{14}{14} - 5 \approx \frac{12}{14}$$

Address-AN Effective Fluence (shadow)

- March-2 arithmetic:**
- Step 1: up - write 0
 - Step 2: up - read 0, write 1, read 1
 - Step 3: up - read 1, write 0, read 0
 - Step 4: down - read 0, write 1, read 1
 - Step 5: down - read 1, write 0, read 0
 - Step 6: down - read 0

$$\text{Efficiency Factor(EF)} = \frac{T_{\text{eff}}}{T_{\text{total}}} = \frac{13}{14}$$

$$\text{Effective Fluence} = \text{Actual Fluence} \times \text{EF}$$

Outline

- ◆ A general BMTI introduction
- ◆ Using built-in self-test (BIST) structures for SEE test
- ◆ **SEE failure analysis with laser**
- ◆ Test method for distinguishing SEU and SET, and SET analysis

Using laser for SEE test

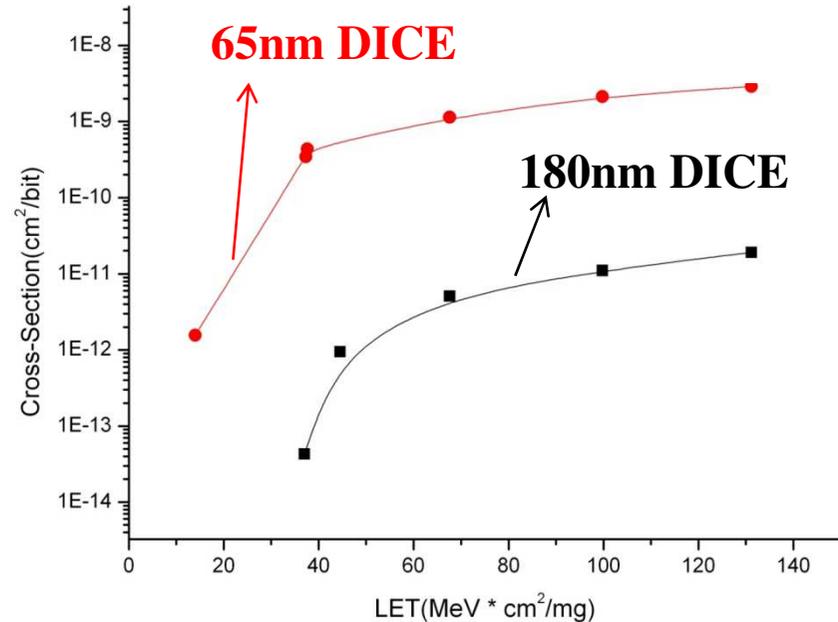
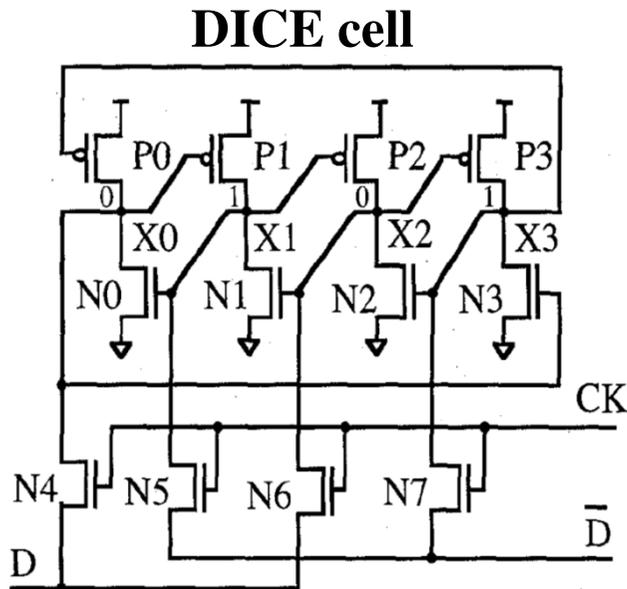
- Pulsed laser is a good tool to estimate SEE performance of ICs
- In BMTI, we mainly take advantage of laser for:

Positioning of SEE errors/failures



Positioning of SEE errors/failures

① Positioning of SEU Sensitive Node in an SEU-hardened SRAM

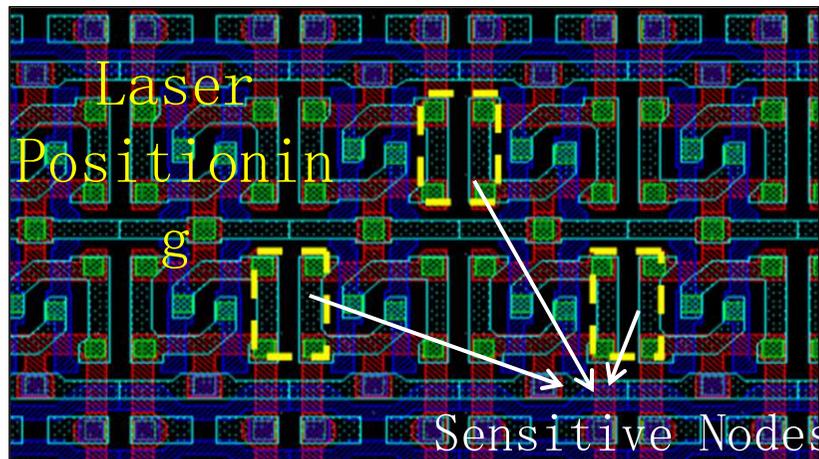


Heavy ion test shows:

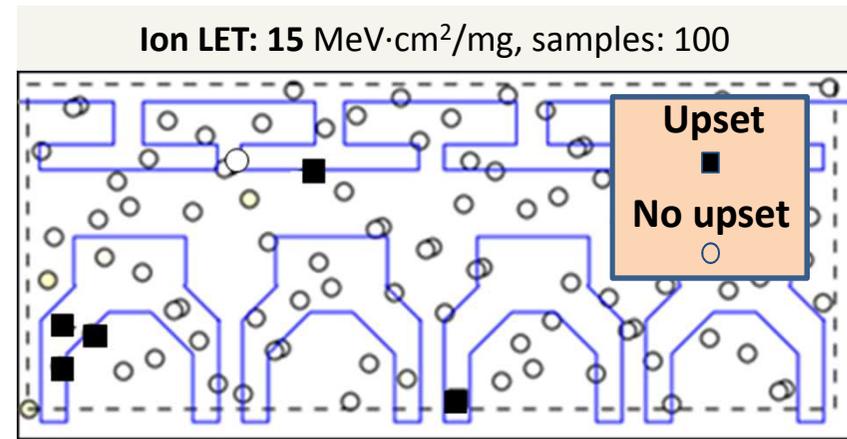
- For a 0.18μm conventional DICE, $LET_{th} \approx 37 \text{ MeV} \cdot \text{cm}^2/\text{mg}$
- For a 65nm conventional DICE, $LET_{th} < 14 \text{ MeV} \cdot \text{cm}^2/\text{mg}$

Positioning of SEE errors/failures

① Positioning of SEU Sensitive Node in an SEU-hardened SRAM



Three areas in a bit cell susceptible to SEUs were found by laser testing.

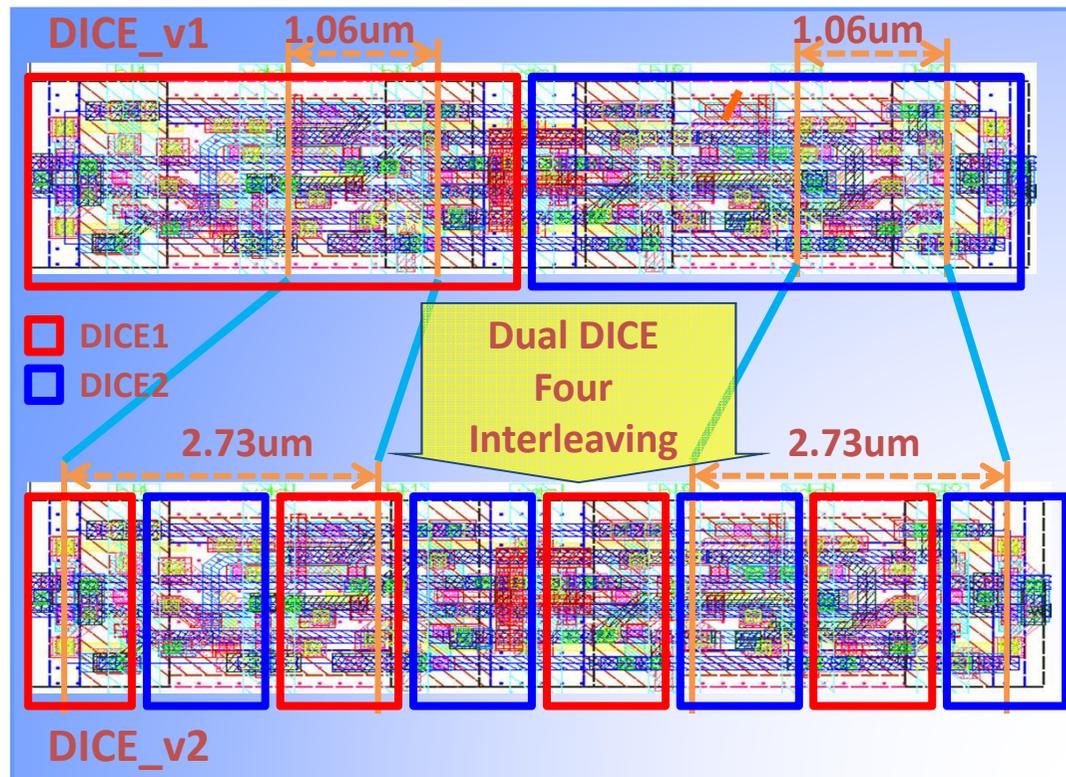


According to the laser result, TCAD simulation gives the reasons for the sensitivity:

- Charge sharing between NMOS
- Charge sharing between NMOS and PMOS, and the bipolar amplification of the PMOS

Positioning of SEE errors/failures

① Positioning of SEU Sensitive Node in an SEU-hardened SRAM



According to laser and simulation analysis, the SRAM was redesigned by modifying its bit cell:

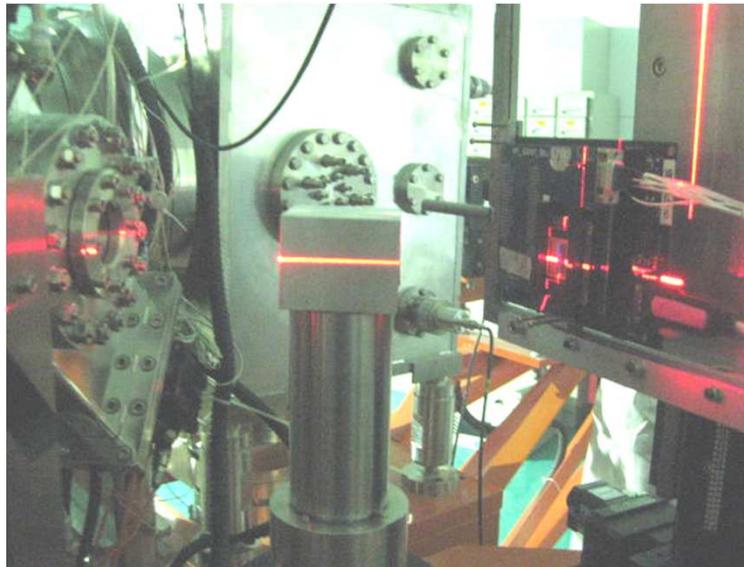
- Spacing between sensitive nodes increases by 2.7x in an area-efficient manner
- Negligible cost of power and performance

Heavy ion test shows that the SEU threshold LET of the new SRAM is greater than $37 \text{ MeV}\cdot\text{cm}^2/\text{mg}$

Positioning of SEE errors/failures

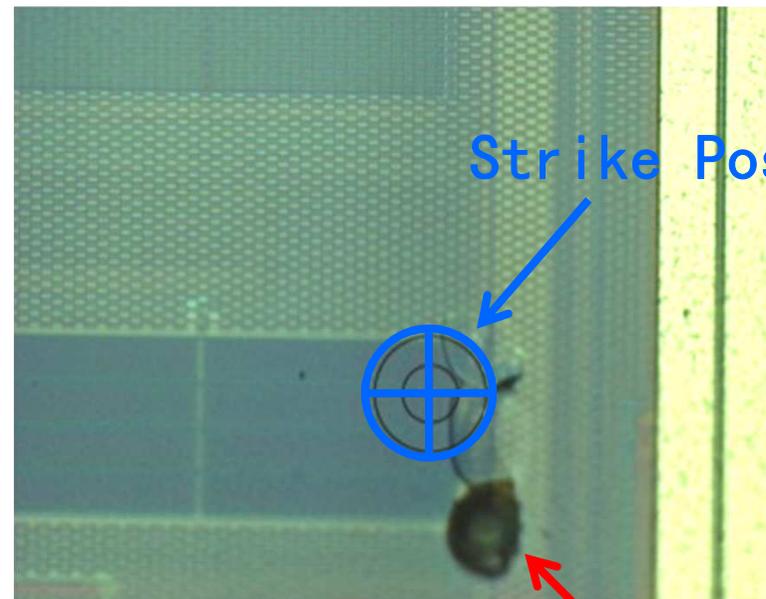
② Failure Analyzing of SEE-induced Burnout

An ADC was burned out under heavy ion irradiation



HIRFL-Accelerator Bi
(LET=93 MeV·cm²/mg)

Microscopy shows that:
ESD transistor and the inter-connection around it was burned



Burn Position

Positioning of SEE errors/failures

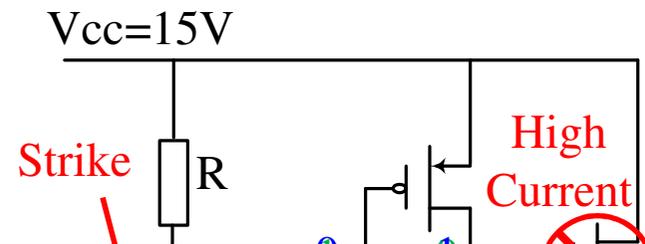
② Failure Analyzing of SEE-induced Burnout

Laser test shows that:

- Direct strike on the ESD transistor doesn't induce burn-out
- Burn-out was found after the strike on the capacitor in the ESD structure

Mechanism Analysis:

The capacitor in the ESD structure can be broken down by irradiation, leading to large current and then burnout



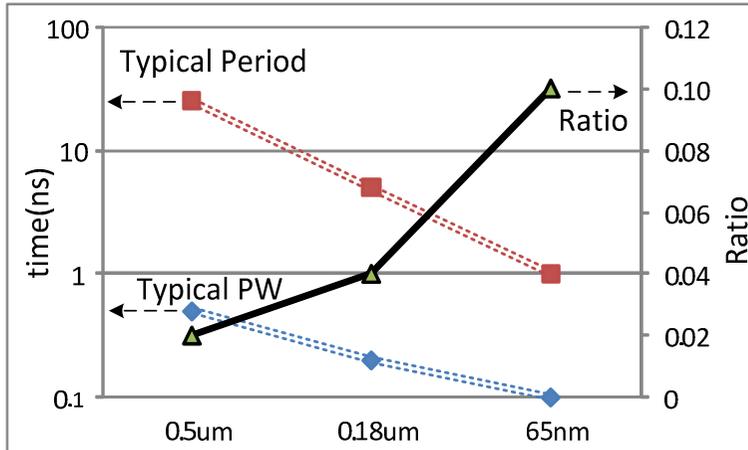
Ion test is difficult to position a failure source when the failure mode and the source node are different, while laser test can do this well.

Outline

- ◆ A general BMTI introduction
- ◆ Using built-in self-test (BIST) structures for SEE test
- ◆ SEE failure analysis with laser
- ◆ **Test method for distinguishing SEU and SET, and SET analysis**

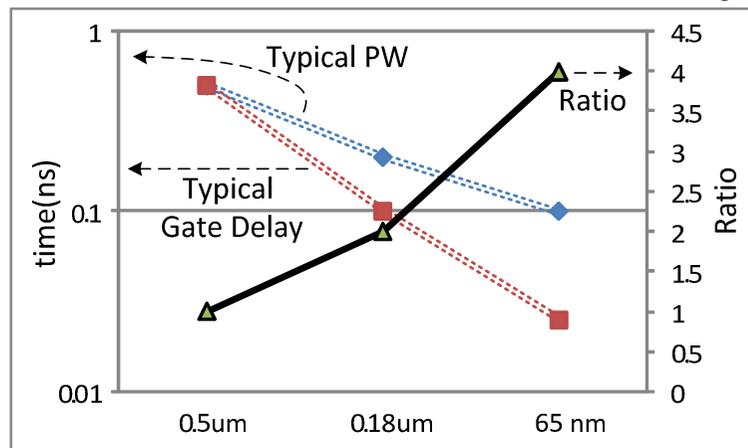
SET has become a serious problem

Pulse Width vs. Period



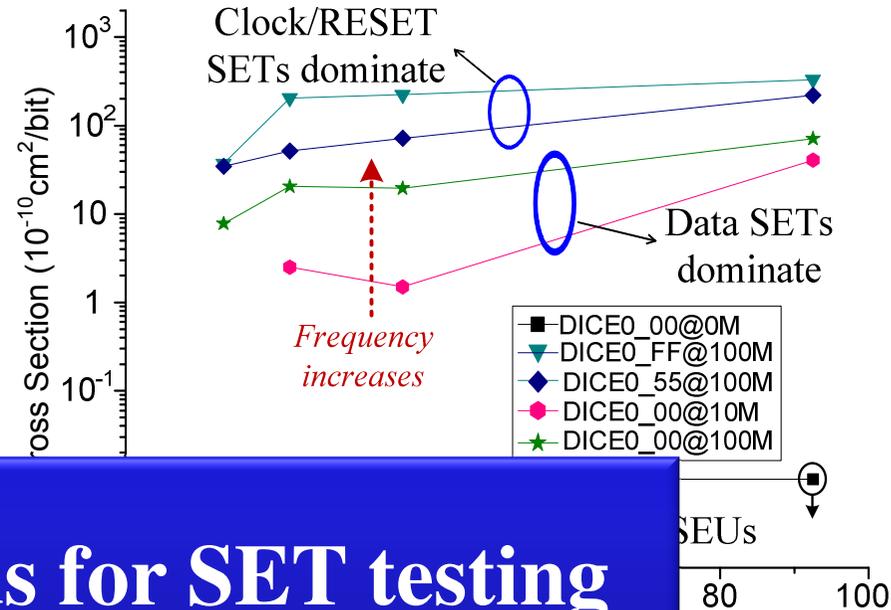
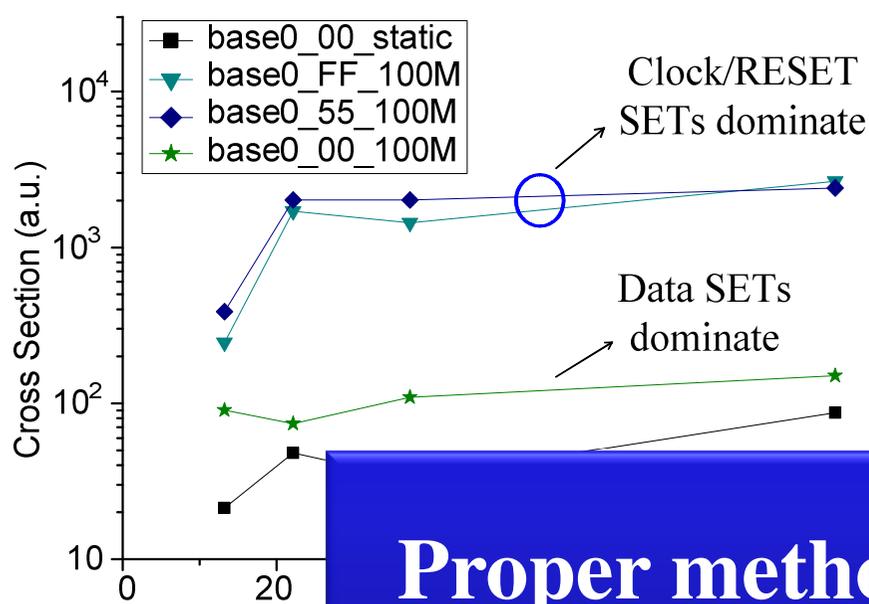
➤ As process technology advances, the ratio of typical SET pulse width (PW) and typical circuit period increases, making SETs easier to be captured by sequential cells

Pulse Width vs. Gate Delay



➤ The ratio of typical SET PW and typical cell delay increases, making SETs easier to propagate on logic paths

65nm Test Results – SET vs. SEU



Proper methods for SET testing are necessary for advanced ICs!

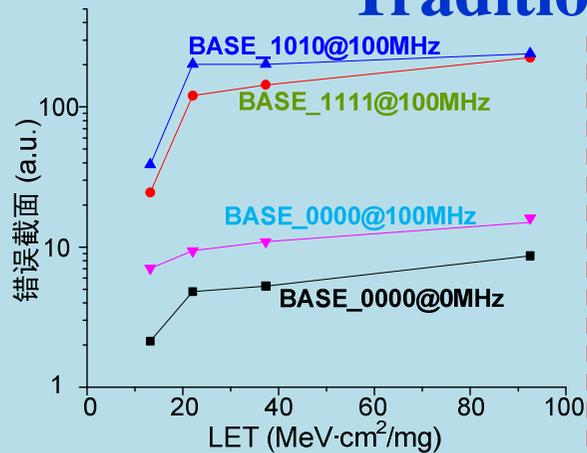
An un

F chain

- For a 65nm unhardened circuit, SET surpasses SEU, and becomes the dominate error source
- For a 65nm hardened circuit, SET is almost the only error source

Method for distinguishing SEU and SET

Traditional SEE Test and Analysis Method



- ① Record total errors after a certain fluence irradiation
- ② Cross Section = Errors/Fluence
- ③ Plot Cross Section with LET

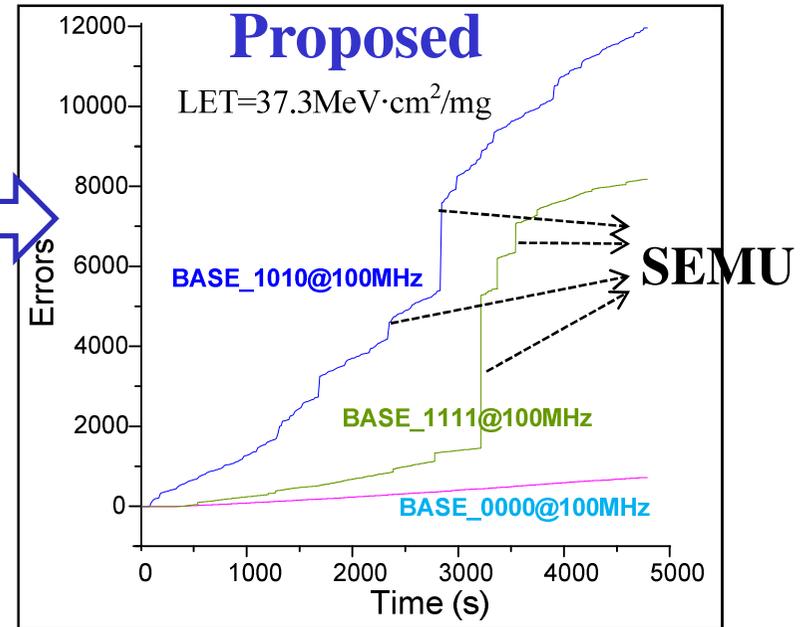
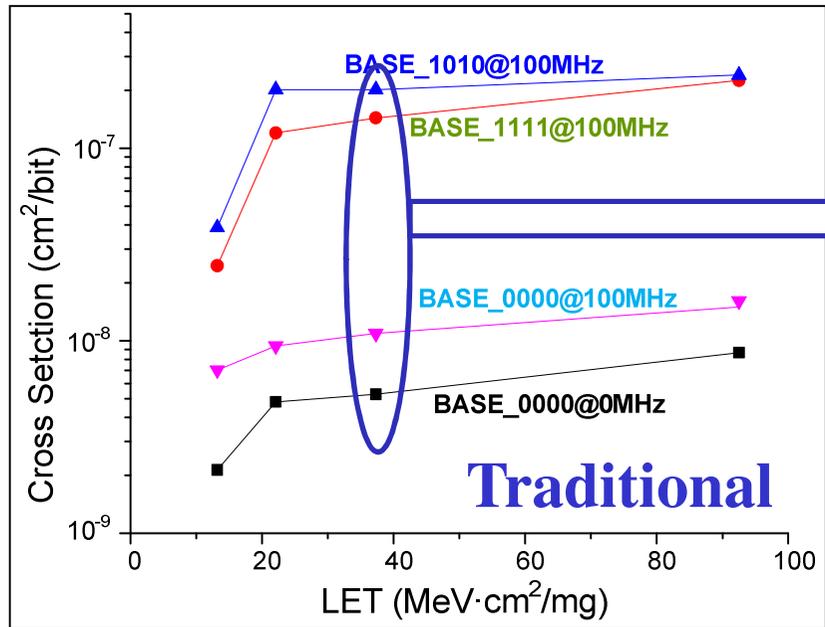
Problem:

- ✓ Unable to see how errors accumulate
- ✓ Unable to distinguish SEU and SET

Time domain test and analysis

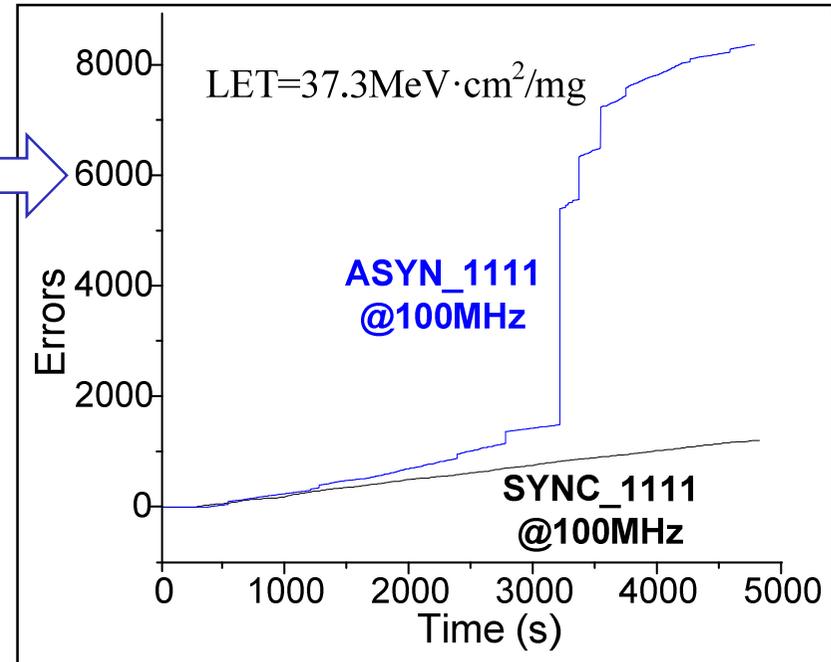
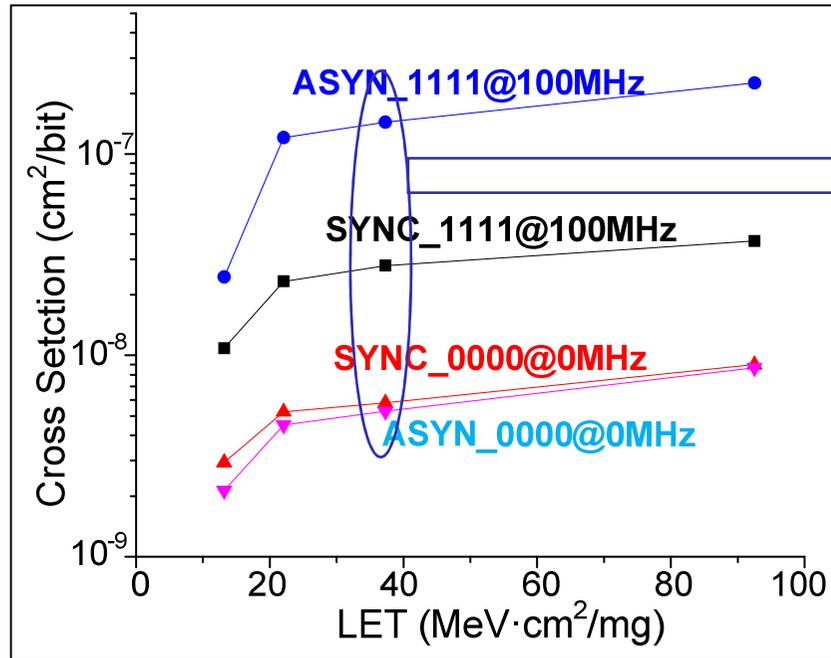
- Record errors every Δt during irradiation
- $\Delta t \leq 0.1s$ to make sure only one event happens during Δt
- Plot error accumulation with time for each type of ions
- SEU and SET can be distinguished by observing time-domain plot

Method for distinguishing SEU and SET



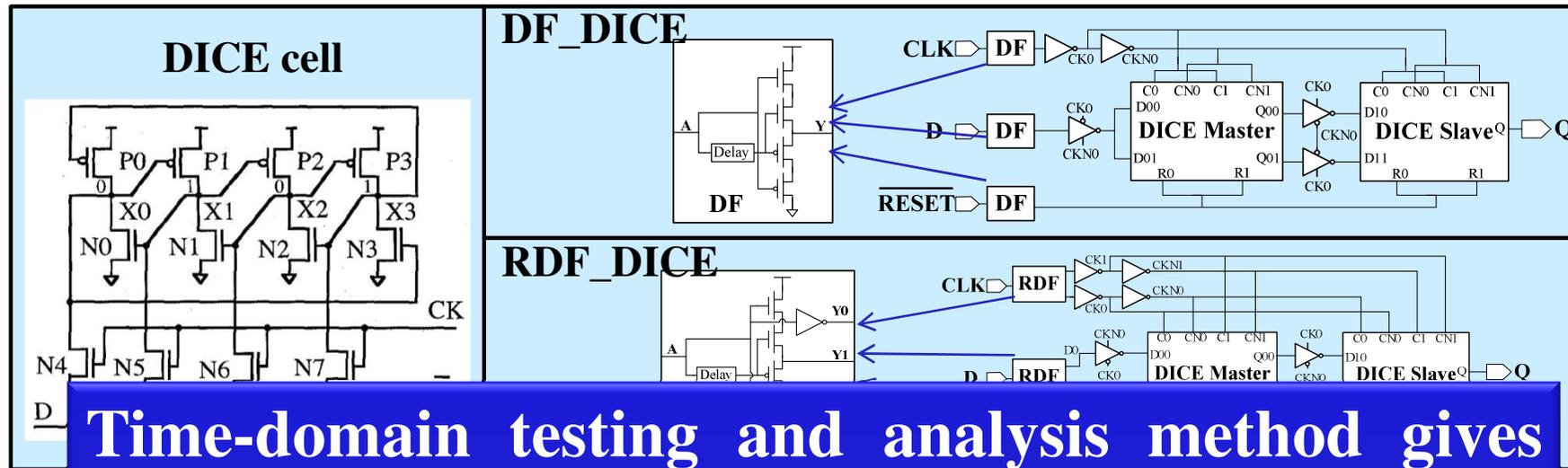
- ❑ Plotting errors in time domain provides insight to the detailed process of error accumulation
- ❑ Discrete jumps in the time-domain curves indicate single-event multiple-cell upsets (SEMUs)
- ❑ Single events on global signals such as clock and reset can cause SEMUs (as large as several thousand upsets)

65nm SET– sync reset vs. async reset

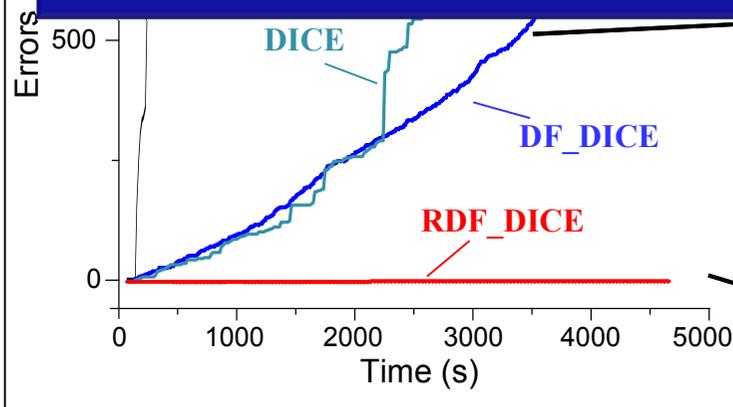


- Many SET-induced SEMUs happened in the test structure with asynchronous reset
- No SEMU was observed in the test structure with synchronous reset

An application in SEE hardness evaluation



Time-domain testing and analysis method gives more information without additional beam time and cost. It helps better recognize and mitigate SEUs and SETs.



method (delay filter) is useful to mitigate SEMUs but still vulnerable to SETs

Redundant delay filter (RDF) removes SETs completely

Outline

- ◆ A general BMTI introduction
- ◆ Using built-in self-test (BIST) structures for SEE test
- ◆ SEE failure analysis with laser
- ◆ Test method for distinguishing SEU and SET, and SET analysis

Summary

Radiation assurance test is very interesting, but also very complicated. It always needs joint efforts to find better solutions, and BMTI is looking forward to collaborating with related partners to do this.



THANK YOU!

BMTI

BMTI

BMTI

BMTI